



**Docket No.1539.1002RE**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

**In re Reissue Application of**

Tomowaki TAKAHASHI

Serial No.: 09/659,375

Group Art Unit: 2872

Filed: September 8, 2000

Examiner: J. Henry

For: CATADIOPTRIC PROJECTION SYSTEMS

## **AMENDMENT**

**Assistant Commissioner for Patents  
Washington, D.C. 20231**

Siri

This is responsive to the Office Action mailed October 31, 2001, having a shortened period for response set to expire on January 31, 2002.

The following amendment and remarks are respectfully submitted.

## **IN THE CLAIMS:**

Please **AMEND** claim 58, as follows.

55 58. (ONCE AMENDED) A method for projecting a pattern from a reticle onto a substrate, comprising:

transmitting light from the reticle through a first imaging system, where the transmitted light pass through a singlepass lens group and a double-pass lens group to a concave mirror, and the light is reflected from the concave mirror back through the double-pass lens group toward the single-pass lens group;

separating the light propagating through the doublepass lens group to the concave mirror from the light propagating through the double-pass lens group from the concave mirror;

with the first imaging system, forming an intermediate image of the pattern between the first imaging system and [the] a second imaging system;

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